

Atty. Dkt. No.	M#	Client Ref.
	306794	P-0388.010-US

**INFORMATION DISCLOSURE STATEMENT  
 BY APPLICANT**

Applicant: BAKKER et al.	
Appl. No.: TO BE ASSIGNED	
Filing Date: November 21, 2003	
Examiner:	Group Art Unit:

Date: November 21, 2003 Page 1 of 1

**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					
	OR					

**FOREIGN PATENT DOCUMENTS**

		Document Number	Date MM/YYYY	Country	Inventor Name	Abstract		Readily Available	
						Enclosed	No	Enclose	No
HN	PR	EP 1 182 510 A1	02/2002	Europe	MOORS et al.	X			
	QR								
	RR								
	SR								
	TR								
	UR								
	VR								

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

HN	WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," J. Vac. Sci. Technol. B 12(6):3833-3840, XP-002096163 (1994)				
	XR					
	YR					
	ZR					
	AAR					
	BBR					
	CCR					

Examiner H. Nguyen Date Considered: 8/4/2004

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.